L Number	Hits	Search Text	DB	Time stamp
1	960	etch\$3 same silicide and ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") and (HCl Cl2 "Cl.sub.2") and (CO H2	USPAT; US-PGPUB;	2003/12/03 20:44
		"H.sub.2" N2 "N.sub.2"))	EPO; JPO; DERWENT; IBM_TDB	
2	210	etch\$3 same silicide and ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") same (HCl Cl2 "Cl.sub.2") same (CO H2 "H.sub.2" N2 "N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/03 20:07
3	50	etch\$3 same silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") same (HCl Cl2 "Cl.sub.2") same (CO H2 "H.sub.2" N2 "N.sub.2"))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/03 20:07
4	20	etch\$3 same silicide same ((CF4 "CF.sub.4") same (Cl2 "Cl.sub.2") same (N2 "N.sub.2"))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/03 20:07
5	10	etch\$3 same silicide same ((CF4 "CF.sub.4") with (CI2 "CI.sub.2") with (N2 "N.sub.2"))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/03 20:08
6	8	etch\$3 with silicide same ((CF4 "CF.sub.4") with (Cl2 "Cl.sub.2") with (N2 "N.sub.2"))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/03 20:19
7	2	(etch\$3 same silicide same ((CF4 "CF.sub.4") with (Cl2 "Cl.sub.2") with (N2 "N.sub.2"))) not (etch\$3 with silicide same ((CF4 "CF.sub.4") with (Cl2 "Cl.sub.2") with (N2 "N.sub.2"))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/03 20:21
8	10	(etch\$3 same silicide same ((CF4 "CF.sub.4") same (Cl2 "Cl.sub.2") same (N2 "N.sub.2"))) not (etch\$3 same silicide same ((CF4 "CF.sub.4") with (Cl2 "Cl.sub.2") with (N2 "N.sub.2"))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/03 20:27
9	6	((etch\$3 same silicide same ((CF4 "CF.sub.4") same (Cl2 "Cl.sub.2") same (N2 "N.sub.2"))) not (etch\$3 same silicide same ((CF4 "CF.sub.4") with (Cl2 "Cl.sub.2") with (N2 "N.sub.2"))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT;	2003/12/03 20:31
10	30)) and (sidewall passi\$7) (etch\$3 same silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") same (HCl Cl2 "Cl.sub.2") same (CO H2 "H.sub.2" N2 "N.sub.2"))) not (etch\$3 same silicide same ((CF4 "CF.sub.4") same (Cl2 "Cl.sub.2") same (N2 "N.sub.2"))	IBM_TDB USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:31
12	0	(etch\$3 with silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") with (HCI Cl2 "CI.sub.2") with (CO H2 "H.sub.2" N2 "N.sub.2"))) not (etch\$3 same silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") same (HCI Cl2 "CI.sub.2") same (CO H2 "H.sub.2" N2 "N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:45
11	16) etch\$3 with silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") with (HCl Cl2 "Cl.sub.2") with (CO H2 "H.sub.2" N2 "N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:47

13	22	etch\$3 same silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") with (HCl Cl2 "Cl.sub.2") with (CO H2 "H.sub.2" N2 "N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:47
14	6	(etch\$3 same silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") with (HCl Cl2 "Cl.sub.2") with (CO H2 "H.sub.2" N2 "N.sub.2"))) not (etch\$3 with silicide same ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6 "SF.sub.6") with (HCl Cl2 "Cl.sub.2") with (CO H2 "H.sub.2" N2 "N.sub.2"))	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2003/12/03 20:47

L Number	Hits	Search Text	DB	Time stamp
1	750	etch\$3 same (SiO2 "SiO.sub.2" Si3N4 "Si.sub.3 N.sub.4"	USPAT;	2003/12/03 21:05
		silicon adj (oxide nitride)) and ((CF4 "CF.sub.4" NF3	US-PGPUB;	
		"NF.sub.3" SF6 "SF.sub.6") same (HCl Cl2 "Cl.sub.2") same	EPO; JPO;	
1		(CO H2 "H.sub.2" N2 "N.sub.2" passi\$7))	DERWENT;	
			IBM_TDB	
2	593	etch\$3 with (SiO2 "SiO.sub.2" Si3N4 "Si.sub.3 N.sub.4" silicon	USPAT;	2003/12/03 21:10
!		adj (oxide nitride)) and ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6	US-PGPUB;	
1		"SF.sub.6") same (HCl Cl2 "Cl.sub.2") same (CO H2 "H.sub.2"	EPO; JPO;	
İ		N2 "N.sub.2" passi\$7))	DERWENT;	
			IBM_TDB	0000/40/00 04 05
3	104	etch\$3 with (SiO2 "SiO.sub.2" Si3N4 "Si.sub.3 N.sub.4" silicon	USPAT;	2003/12/03 21:05
		adj (oxide nitride)) same ((CF4 "CF.sub.4" NF3 "NF.sub.3"	US-PGPUB;	
		SF6 "SF.sub.6") with (HCl Cl2 "Cl.sub.2") with (CO H2	EPO; JPO;	
		"H.sub.2" N2 "N.sub.2" passi\$7))	DERWENT;	
1.		A LOO CIL COLOO HOLO CILO DE OLO CILO LA CILO CILO DE CILO CILO CILO CILO CILO CILO CILO CILO	IBM_TDB	0000/40/00 04:40
4	58		USPAT;	2003/12/03 21:10
1		adj (oxide nitride)) with ((CF4 "CF.sub.4" NF3 "NF.sub.3" SF6	US-PGPUB;	
		"SF.sub.6") with (HCI Cl2 "Cl.sub.2") with (CO H2 "H.sub.2" N2	EPO; JPO; DERWENT;	}
		"N.sub.2" passi\$7))	IBM TDB	
_	15	ALLES with (CiOO VCiO out OV CiONA VCi out 2 N out 4" oilioon	USPAT:	2003/12/03 21:09
5	าอ	etch\$3 with (SiO2 "SiO.sub.2" Si3N4 "Si.sub.3 N.sub.4" silicon adj (oxide nitride)) with ((CF4 "CF.sub.4") with (CI2 "CI.sub.2")	US-PGPUB:	2003/12/03 21:09
		with (N2 "N.sub.2"))	EPO; JPO;	
		With (NZ N.Sub.Z))	DERWENT;	
			IBM TDB	
6	43	(etch\$3 with (SiO2 "SiO.sub.2" Si3N4 "Si.sub.3 N.sub.4"	USPAT:	2003/12/03 21:09
0	40	silicon adj (oxide nitride)) with ((CF4 "CF.sub.4" NF3	US-PGPUB;	2000/12/00 21/00
		"NF.sub.3" SF6 "SF.sub.6") with (HCl Cl2 "Cl.sub.2") with (CO	EPO; JPO;	
	!	H2 "H.sub.2" N2 "N.sub.2" passi\$7))	DERWENT;	Ì
) not (etch\$3 with (SiO2 "SiO.sub.2" Si3N4 "Si.sub.3 N.sub.4"	IBM_TDB	
		silicon adj (oxide nitride)) with ((CF4 "CF.sub.4") with (CI2	<u>-</u> ,	
1		"Cl.sub.2") with (N2 "N.sub.2"))		j
)		_